



Form PTO 1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY DOCKET NO. 287990US2PCT	SERIAL NO. 10/572,353
LIST OF REFERENCES CITED BY APPLICANT		APPLICANT Jean-Charles GUIBERT	
		FILING DATE March 16, 2006	GROUP

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
AA	2003/0104287	6/5/2003	YUASA, Mitsuhiro			
AB	6 416 908	7/9/2002	KLOSNER, Marc A. et al.			
AC	6 375 870	4/23/2002	VISOVSKY, Nick J. et al.			
AD	5 281 511	1/25/1994	GERHARDT, Joergen			
AE						
AF						
AG						
AH						
AI						
AJ						
AK						
AL						
AM						
AN						

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	NO
AO	199 13 683	11/25/1999	DE(equivalent of US 6 455 429)		NO
AP	0 845 710	8/3/1998	EP(with English abstract)		NO
AQ					
AR					
AS					
AT					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

AU	RUCHHOEFT, P. et al., "Patterning curved surfaces: Template generation by ion beam proximity lithography and relief transfer by step and flash imprint lithography", Journal of Vacuum Science and Technology, Vol. 17, No. 6, Pages 2965-2969, 1999.
AV	ROGERS, J.A. et al., "Printing, molding, and near-field photolithographic methods for patterning organic lasers, smart pixels and simple circuits", Synthetic Metals, Vol. 115, No. 1-3, Pages 5-11, 2000.
AW	ROOS, Nijs et al., "Nanolimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing", Proceedings of The SPIE, Vol. 4343, Pages 427-435, 2001.
AX	CHOU, Stephen Y. et al., "Imprint of sub-25 nm Vias and trenches in polymers", Appl. Phys. Lett. Vol. 67, No. 21, Pages 3114-3116, 20 November 1995.
AY	TAN, Hua et al., "Roller nanolimprint lithography", J. Vac. Sci. Technol. Vol. 16, No. 6, Pages 3926-3928, 1998.
AZ	GUIBERT, Jean-Charles, "Nanotechnologies and nanolithography in Europe", Pages xxi-xxx.

Additional References sheet(s) attached

Examiner /Jonathan Jelsma/

Date Considered 03/18/2009

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.